


<b>Search Notes</b> 	<b>Application/Control No.</b> 10693854	<b>Applicant(s)/Patent Under Reexamination</b> RELYEA ET AL.
	<b>Examiner</b> Wang, Ben C	<b>Art Unit</b> 2192

<b>SEARCHED</b>			
<b>Class</b>	<b>Subclass</b>	<b>Date</b>	<b>Examiner</b>
717	109	03/27/2007	Ben C. Wang

<b>SEARCH NOTES</b>		
<b>Search Notes</b>	<b>Date</b>	<b>Examiner</b>
EAST Databases Search	03/27/2007	Ben C. Wang
NPL Databases Search	10/20/2007	Ben C. Wang

<b>INTERFERENCE SEARCH</b>			
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